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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/645,903	08/25/2000	Li Li	3361.2US (97-663.2)	6825

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EXAMINER

GUERRERO, MARIA F

ART UNIT PAPER NUMBER

2822

DATE MAILED: 03/05/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

<b>Office Action Summary</b>	<b>Application No.</b>	<b>Applicant(s)</b>	
	09/645,903	LI, LI	
	<b>Examiner</b>	<b>Art Unit</b>	
	Maria Guerrero	2822	

**-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --**

**Period for Reply**

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

**Status**

- 1) ☒ Responsive to communication(s) filed on 10 February 2004.
- 2a) ☐ This action is **FINAL**.                      2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

**Disposition of Claims**

- 4) ☒ Claim(s) 1-6,8 and 9 is/are pending in the application.
- 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration.
- 5) ☐ Claim(s) \_\_\_\_\_ is/are allowed.
- 6) ☒ Claim(s) 1-6,8 and 9 is/are rejected.
- 7) ☐ Claim(s) \_\_\_\_\_ is/are objected to.
- 8) ☐ Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement.

**Application Papers**

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on \_\_\_\_\_ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.  
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).  
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

**Priority under 35 U.S.C. § 119**

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All    b) ☐ Some \*    c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. \_\_\_\_\_.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- \* See the attached detailed Office action for a list of the certified copies not received.

**Attachment(s)**

- |  |   |
|--|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892)   | 4) <input type="checkbox"/> Interview Summary (PTO-413)<br>Paper No(s)/Mail Date. _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948)   | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152)             |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)<br>Paper No(s)/Mail Date <u>2-10-04</u> . | 6) <input type="checkbox"/> Other: _____  |

### **DETAILED ACTION**

1. This Office Action is in response to the Amendment filed December 12, 2003 and the Request for continued examination filed February 10, 2004.

Claim 7 is canceled.

Claims 1-6 and 8-9 are pending.

#### ***Continued Examination Under 37 CFR 1.114***

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on February 10, 2004 has been entered.

#### ***Information Disclosure Statement***

2. The information disclosure statement (IDS) submitted on February 10, 2004 has been considered.

#### ***Claim Rejections - 35 USC § 103***

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

3. Claims 1-6 and 8-9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jin et al. (U.S. 5,883,001) in view of Wilson et al. (U.S. 4,943,359).

Art Unit: 2822

Jin et al. teaches a contact opening in a dielectric layer extending from an upper surface of the dielectric layer to a substantially damage free metal-containing conductive pad having substantially parallel sidewalls (Fig. 8, col. 7, lines 29-31, 45-49). Jin et al. teaches a contact opening in a dielectric layer and a barrier layer, the semiconductor substrate having a substantially damage free metal-containing conductive pad under the dielectric layer and the barrier layer. Jin et al. also shows the residues being removed from the contact opening (residues free) (Fig. 8, col. 2, lines 55-60, col. 7, lines 45-49). In addition, Jin et al. teaches employing a fluorine-containing compound (col. 7, lines 49-50).

Regarding the limitations “the metal-containing conductive pad substantially free of charging damage”; Jin et al. teaches that no oxide residue remains on the pads. Jin et al. also teaches limiting the dry etch time to avoid the charging damage (Fig. 8, col. 2, lines 55-65, col. 7, lines 45-62, col. 8, lines 25-30, col. 10, lines 5-12). Therefore, the metal-containing conductive pad taught by Jin et al. is substantially free of charging damage.

Regarding the limitations “a metal polymer residue-free and oxide polymer residue free contact”; Jin et al. teaches the contact opening being residues free (Fig. 8, col. 2, lines 55-60, col. 7, lines 45-49). Therefore, there is not metal polymer residue or oxide polymer residue in the contact opening.

Jin et al. does not specifically show removing the residues by applying nitric acid and phosphoric acid. However, Wilson et al. shows that the use of nitric acid and

Art Unit: 2822

phosphoric acid for the removing of residues is well known in the art (col. 4, lines 35-38).

Furthermore, product-by-process claims are limited and defined by the process; determination of patentability is based on the product itself. The patentability of a product does not depend on its method of production. If the product in the product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior art product was made by a different process. In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976 (footnote 3). See also IN re Brown and Saffer, 173 USPQ 685 (CCPA 1972); In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); In re Marosi et al., 218 USPQ 289 (Fed. Cir. 1983); In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985).

Therefore, it would have been obvious to a person of ordinary skill in the art at the time of the invention to recognize that the structure taught by Jin et al. would correspond with the structure claimed.

### ***Response to Arguments***

4. Applicant's arguments filed December 12, 2003 have been fully considered but they are not persuasive. Claims 1-6 and 8-9 stand rejected. Claim Rejections 35 USC 112, first paragraph are withdrawn.

Applicant argued that the combination of Jin et al. and Wilson et al. fails to teach an opening in a dielectric layer having substantially parallel sidewalls. However, Jin et

Art Unit: 2822

al. shows a contact opening in a dielectric layer extending from an upper surface of the dielectric layer to a substantially damage free metal-containing conductive pad having substantially parallel sidewalls (Fig. 8, col. 7, lines 29-31, 45-62, col. 8, lines 25-30, col. 10, lines 5-12).

Applicant argued that the combination of Jin et al. and Wilson et al. fails to teach all claim limitations. However, the patentability of a product does not depend on its method of production. If the product in the product-by process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior art product was made by a different process. In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976 (footnote 3)). See also IN re Brown and Saffer, 173 USPQ 685 (CCPA 1972); In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); In re Marosi et al., 218 USPQ 289 (Fed. Cir. 1983); In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985).

Applicant argued that Jin fails to teach or suggest the substantially damage free metal containing conductive pad because Jin acknowledges the main etch and overetch may induce charging damage. However, Jin et al. also teaches limiting the dry etch time to avoid the charging damage and producing excellent reliability (Fig. 8, col. 2, lines 55-65, col. 7, lines 45-62, col. 8, lines 25-30, col. 10, lines 5-12). Therefore, the metal-containing conductive pad taught by Jin et al. is substantially free of charging damage.

Furthermore, a person of ordinary skill in the art at would recognize that the structure taught by Jin et al. would correspond with the structure claimed because there is not evidence establishing an unobvious difference between the claimed product and

Art Unit: 2822


the prior art product. In re Marosi, 710 F.2d 798, 802, 218 USPQ 289, 292 (Fed. Cir. 1983).

***Conclusion***

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Maria Guerrero whose telephone number is 571-272-1837.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

  
Maria Guerrero  
Primary Examiner  
March 1, 2004